HORIBA Scientific

Plasma Process Engineering: Twin Mode

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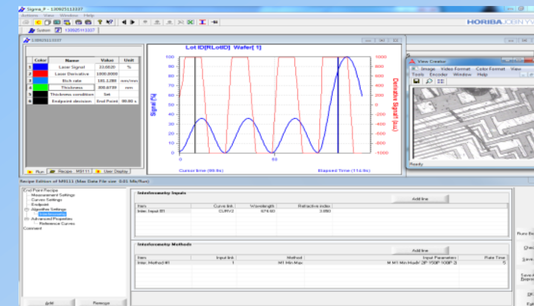
Why not

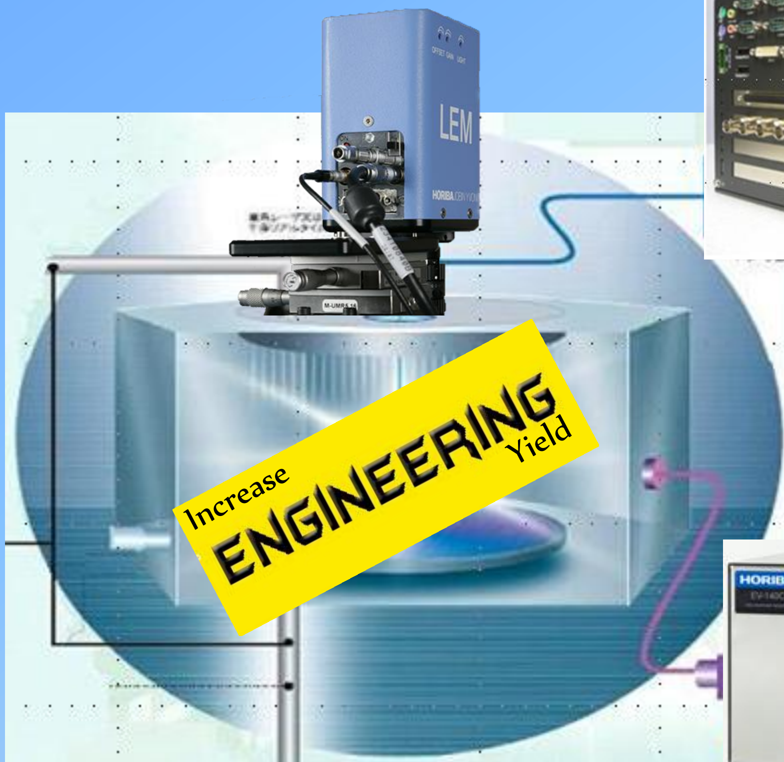
- **Plasma Control** (Optical Emission Spectroscopy)
- **Etch rate measurement** (Interferometry)

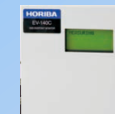
in a single Endpoint Instrument ?

LEM camera

- Local measurement on sample
- Laser spot # 50 µm
- VIS 670 nm or IR 905 nm

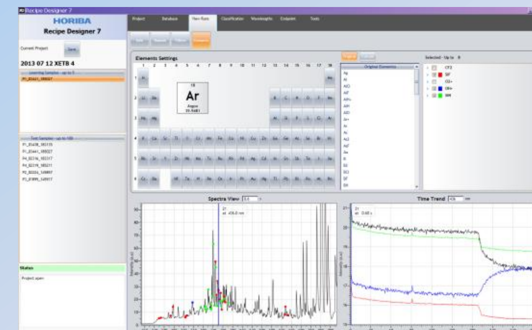






EV-140

- Global Plasma Monitoring
- high grade spectrometer
- [200, 800] nm



Only 1 PC controller (Win7)

- Both sensors simultaneously
- 1 real-time software
- Engineering add-ons

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